

Form 1449 (Modified)			
Information Disclosure Statement By Applicant (Use Several Sheets if Necessary)		Atty Docket No. NOVLP075/NVLS-000820	Application No.: Unassigned
		Applicant: Tipton et al.	
		Filing Date HEREWITH	Group Unassigned

U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A1	6,329,017	12/11/01	Liu et al.			
	A2	6,383,466	5/7/02	Domansky et al.	423	335	
	A3	6,365,266	4/2/02	MacDougall et al.	428	304.4	
	A4	5,504,042	4/2/96	Cho et al.	438	781	
	A5	5,858,457	1/12/96	Brinker et al.	427	162	
	A6	6,270,846	8/7/01	Brinker et al.	427	385.5	
	A7	6,387,453	5/14/02	Brinker et al.	427	387	
	A8	6,420,441	10/10/99	Allen et al.	521	77	
	A9	6,271,273	10/10/00	You et al.	521	61	

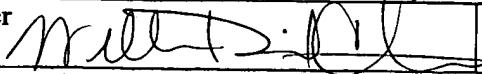
Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
	B1							

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	C1	Liu et al., "Mesoporous Silica Film From a Solution Containing a Surfactant and Methods of Making Same," U.S. Patent Application Publication No. US2002/0034626, Published March 21, 2002, 27 Pages
	C2	Wu et al., "Use of Multifunctional SI-Based Oligomer/Polymer for the Surface Modification of Nanoporous Silica Films," U.S. Patent Application Publication No. US2002/0001973, Published January 3, 2002, 13 Pages
	C3	Cho et al., "Plasma Treatments of Molecularly Tempered Nanoporous Silica Films," Electrochemical and Solid-State Letters, 4 (4) G35-G38 (2001)
	C4	Yung et al., "Spin-on Mesoporous Silica Films with Ultralow Dielectric Constants, Ordered Pore Structures, and Hydrophobic Surfaces," Adv. Mater. 2001, 13, No. 14, 1099-1102
	C5	Schulberg et al., "System for Deposition of Mesoporous Materials," U.S. Patent Application No. 10/295,965, filed November 15, 2002, 64 Pages
	C6	Watkins et al., "Mesoporous Materials and Methods," U.S. Patent Application No. 10/301,013, filed November 21, 2002, 34 Pages

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	C7	Justin F. Gaynor, "In-Situ Treatment of Low-K Films With a Silylating Agent After Exposure To Oxidizing Environments," U.S. Patent Application No.10/056,926 filed January 24, 2002, 34 Pages
	C8	Gangpadhyay et al., "The First International Surface Cleaning Workshop," Northeastern University, November 11-14, 2002
Examiner 	Date Considered	9/01/2004

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.